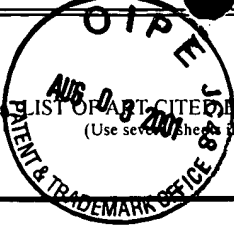

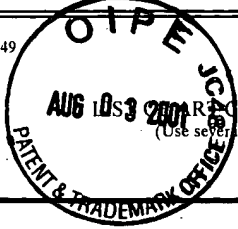
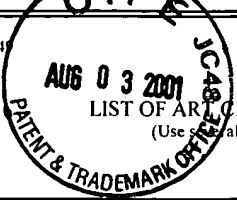


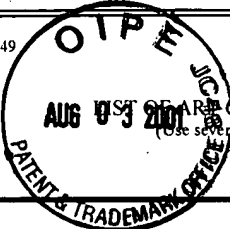
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| 200. Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | ATTY. DOCKET NO. MI22-1035 | | SERIAL NO. 09/234,233 | |
|  | | | | LIST OF ARTS CITED BY APPLICANT (Use several sheets if necessary) | | | |
| | | | | APPLICANT Weimin Li | | FILING DATE January 20, 1999 | |
| U.S. PATENT DOCUMENTS | | | | | | | |
| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | |
| DV | AA | 5,883,011 | 4/1999 | Lin et al | | | |
| | AB | 5,677,015 | 10/1994 | Hasegawa | | | |
| | AC | 5,783,493 | 7/1998 | Yeh et al | | | |
| | AD | 5,807,660 | 9/1998 | Lin et al | | | |
| | AE | 4,833,096 | 5/1989 | Huang et al | | | |
| | AF | 5,405,489 | 4/1995 | Kim et al | | | |
| | AG | 5,470,772 | 11/1995 | Woo | | | |
| | AH | 5,652,187 | 7/1997 | Kim et al | | | |
| | AI | 5,656,337 | 8/1997 | Park et al | | | |
| | AJ | 4,805,683 | 2/1989 | Magdo et al | | | |
| | AK | 5,874,367 | 2/1999 | Dobson | | | |
| DV | AL | | | | | | |
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| | Document Number | Date | Country | Class | Subclass | Translation | |
| | | | | | | Yes | No |
| DV | AM | 06067019A | 9/1999 | Japan (Glass) | | | |
| DV | AN | 9750993 | 2/1997 | Japan | | | |
| DV | AO | 63-157443A | 6/30/1988 | Japan (Morita) | | | |
| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | |
| DV | AP | | TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10. (No date) | | | | |
| | | | | | | | |
| DV | AQ | | TEXT: Wolf, S. et al., "Silicon Processing for the VLSI Era", Vol. 1, pp. 437-441. (No date) | | | | |
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| | AR | | | | | | |
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| EXAMINER <i>ghuland</i> | | | | DATE CONSIDERED <i>10/11/01</i> | | | |
| <p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p> | | | | | | | |

| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | | ATTY. DOCKET NO. MI22-1035 | | SERIAL NO. 09/234,233 | |
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| U.S. PATENT DOCUMENTS | | | | | | | | |
| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | | |
| DV | AA | 5,585,880 | 1/1999 | Dobson et al | | | | |
| | AB | 5,219,613 | 6/1993 | Fabry et al | | | | |
| | AC | 5,270,267 | 12/1993 | Quellet | | | | |
| | AD | 5,541,445 | 7/1996 | Quellet | | | | |
| | AE | 6,022,404 | 2/2000 | Ettlinger et al | | | | |
| | AF | 5,709,741 | 1/1998 | Akamatsu et al | | | | |
| | AG | 4,648,904 | 3/1987 | Depasquale et al | | | | |
| | AH | 4,158,717 | 6/1979 | Nelson | | | | |
| | AI | 5,667,015 | 9/1997 | Harestad et al | | | | |
| | AJ | 5,661,093 | 8/1997 | Ravi et al | | | | |
| | AK | 5,536,857 | 7/1996 | Naula | | | | |
| | AL | 4,695,859 | 9/1987 | Guha et al | | | | |
| | AM | 4,954,867 | 6/1990 | Hosaka | | | | |
| | AN | 5,441,797 | 8/1995 | Hogan | | | | |
| | AO | 5,710,067 | 1/1998 | Foote | | | | |
| | AP | 5,759,755 | 6/1998 | Park et al | | | | |
| | AQ | 5,838,052 | 11/1998 | McTeer | | | | |
| DV | AR | 5,883,011 | 4/1999 | Lin et al | | | | |
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| | Document Number | Date | Country | Class | Subclass | Translation | | |
| | | | | | | Yes | No | |
| DV | AS | 406244172A | 9/1994 | Japan | | | | |
| DV | AT | 593,727 | 10/1947 | GB | | | | |
| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | | |
| EXAMINER <i>Shulard</i> | | | | DATE CONSIDERED <i>10/11/01</i> | | | | |
| *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | | | |

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| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | | ATTY. DOCKET NO. M122-1035 | | SERIAL NO. 09/234,233 | | |
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| U.S. PATENT DOCUMENTS | | | | | | | | | |
| *Examiner Initial | AA | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | | |
| DV | AA | 5,061,509 | 10/1991 | Naito et al | | | | | |
| | AB | 4,600,671 | 7/1986 | Saitoh et al | | | | | |
| | AC | 5,753,320 | 5/1998 | Mikoshiba et al | | | | | |
| | AD | 5,356,515 | 10/1994 | Tahara et al | | | | | |
| | AE | 5,674,356 | 10/07/97 | Nagayama | | | | | |
| | AF | 5,731,242 | 03/24/98 | Parat et al. | | | | | |
| | AG | 5,741,721 | 04/21/98 | Stevens | | | | | |
| | AH | 5,034,348 | 07/23/91 | Hartswick et al. | | | | | |
| | AI | 5,472,829 | 12/05/95 | Ogawa | | | | | |
| | AJ | 5,641,607 | 06/24/97 | Ogawa et al. | | | | | |
| DV | AK | 5,648,202 | 07/15/97 | Ogawa et al. | | | | | |
| | AL | | | | | | | | |
| FOREIGN PATENT DOCUMENTS | | | | | | | | | |
| | | Document Number | Date | Country | Class | Subclass | Translation | | |
| | | | | | | | Yes | No | |
| DV | AM | 5-263255 | 10/1993 | Japan | | | | | |
| DV | AN | 0 471 185 A2 | 7/10/91 | EPO | | | | | |
| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | | | |
| DV | AO | | D.R. McKenzie et al., "New Technology for PACVD", Surface and Coatings Technology, 82 (1996), pp. 326-333. | | | | | | |
| | | | | | | | | | |
| DV | AP | | S. McClatchie et al.; "Low Dielectric Constant Flowfill® Technology For IMD Applications"; undated; 7 pages | | | | | | |
| | | | | | | | | | |
| DV | AQ | | K. Beekmann et al.; "Sub-micron Gap Fill and In-Situ Planarisation using Flowfill™ Technology"; October 1995; pp. 1-7 | | | | | | |
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| EXAMINER <i>Smuland</i> | | | | DATE CONSIDERED 10/11/01 | | | | | |
| <p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p> | | | | | | | | | |

| Form PTO-144 | |  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | | ATTY. DOCKET NO. MI22-1035 | | SERIAL NO. 09/234,233 | |
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| LIST OF ARTS CITED BY APPLICANT (Use additional sheets if necessary) | | | | | APPLICANT Weimin Li | | | |
| | | | | | FILING DATE January 20, 1999 | | GROUP 2818 | |
| U.S. PATENT DOCUMENTS | | | | | | | | |
| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | | |
| DV | AA | 5,670,297 | 09/23/97 | Ogawa et al. | | | | |
| | AB | 5,677,111 | 10/14/97 | Ogawa | | | | |
| | AC | 5,698,352 | 12/16/97 | Ogawa et al. | | | | |
| | AD | 5,831,321 | 11/03/98 | Nagayama | | | | |
| | AE | 5,591,566 | 01/07/97 | Ogawa | | | | |
| | AF | 6,008,124 | 12/28/99 | Sekiguchi et al. | | | | |
| | AG | 5,340,621 | 08/23/94 | Matsumoto et al. | | | | |
| | AH | 5,600,165 | 02/04/97 | Tsukamoto et al. | | | | |
| | AI | 5,872,385 | 02/16/99 | Taft et al. | | | | |
| | AJ | 5,960,289 | 09/28/99 | Tsui et al. | | | | |
| | AK | 5,968,324 | 10/19/99 | Cheung et al. | | | | |
| DV | AL | 6,020,243 | 02/01/00 | Wallace et al. | | | | |
| FOREIGN PATENT DOCUMENTS | | | | | | | | |
| | Document Number | Date | Country | Class | Subclass | Translation | | |
| | | | | | | Yes | No | |
| DV | AM | 0 588 087 A2 | 8/18/93 | EPO | | | | |
| DV | AN | 0 588 087 A3 | 8/18/93 | EPO | | | | |
| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | | |
| DV | AO | A. Kiermasz et al.; "Planarisation for Sub-Micron Devices Utilising a New Chemistry"; Electrotech, February 1995; 2 pages | | | | | | |
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| DV | AP | IBM Technical Disclosure Bulletin "Low-Temperature Deposition of SiO ₂ , Si ₃ N ₄ or SiO ₂ -Si ₃ N ₄ ," Vol. 28, No. 9, p. 4170, Feb. 1986. | | | | | | |
| | | | | | | | | |
| DV | AQ | ARTICLE: Bencher, C. et al., "Dielectric antireflective coatings for DUV lithography", Solid State Technology (March 1997), pp.109-114. | | | | | | |
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| EXAMINER <i>Stuland id</i> | | | | DATE CONSIDERED <i>10/11/01</i> | | | | |
| *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | | | |

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| MUST BE CITED BY APPLICANT (Use several sheets if necessary) | | | | | APPLICANT Weimin Li | | | |
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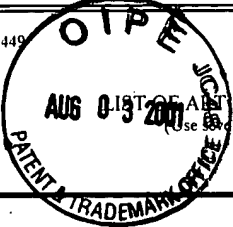
| U.S. PATENT DOCUMENTS | | | | | | | |
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| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | |
| DV | AA | 6,054,379 | 04/25/00 | Yau et al. | | | |
| | AB | 5,948,482 | 09/07/99 | Brinker et al. | | | |
| | AC | 5,800,877 | 09/01/98 | Maeda et al. | | | |
| | AD | 5,260,600 | 11/09/93 | Harada | | | |
| | AE | 4,992,306 | 02/12/91 | Hochberg et al. | | | |
| | AF | 4,702,936 | 10/27/87 | Maeda et al. | | | |
| | AG | 4,863,755 | 09/05/89 | Hess et al. | | | |
| | AH | 5,234,869 | 08/10/93 | Mikata et al. | | | |
| | AI | 5,302,366 | 04/12/94 | Schuetz et al. | | | |
| | AJ | 5,591,494 | 01/07/97 | Sato et al. | | | |
| | AK | 5,968,611 | 10/19/99 | Kaloyeros et al. | | | |
| | AL | 6,159,871 | 12/12/00 | Loboda et al. | | | |
| | AM | 5,744,399 | 4/1998 | Rostoker | | | |
| | AN | 5,883,014 | 3/1999 | Chen | | | |
| DV | AO | 6,017,779 | 1/25/00 | Miyasaka | | | |


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| Document Number | Date | Country | Class | Subclass | Translation | | |
| | | | | | Yes | No | |
| DV AP 09055351 | 25/2/97 | Japan | | | | | |
| DV AQ 0 778 496 A2 | 05/12/96 | EPO | | | | | |

| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | |
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| DV | AR | | Noboru Shibata, "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Japanese Journal of Applied Physics, Vol. 30, No. 5, May 1991, pp. 997-1001. |
| DV | AS | | Julius Grant, Hack's Chemical Dictionary, Fourth Edition, McGraw-Hill Book Company, © 1969, rented by Grant © 1972, pp. 27 |

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| EXAMINER <i>Stuland</i> | DATE CONSIDERED <i>10/11/01</i> |
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|  | | | | | CITED BY APPLICANT <small>(Use several sheets if necessary)</small> | | | |
| | | | | | APPLICANT Weimin Li | | | |
| | | | | | FILING DATE January 20, 1999 | | GROUP 2818 | |
| U.S. PATENT DOCUMENTS | | | | | | | | |
| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | | |
| DV | AA | 5,472,827 | 12/1995 | Ogawa et al. | | | | |
| | AB | 6,156,674 | 12/5/00 | Li et al | | | | |
| | AC | 6,461,003 | 10/24/95 | Haveman | | | | |
| | AD | 6,124,641 | 9/26/00 | Matsura | | | | |
| | AE | 5,554,567 | 9/10/96 | Wang | | | | |
| DV | AF | 6,028,015 | 2/22/00 | Wang | | | | |
| FOREIGN PATENT DOCUMENTS | | | | | | | | |
| | Document Number | Date | Country | Class | Subclass | Translation | | |
| | | | | | | Yes | No | |
| DV | AG | EP 0 464 515 A3/B1 | 08.01.92 | EPO (Mikata et al.) | | | | |
| DV | AH | EP 0 771 886 A1 | 07.05.97 | EPO (Loboda) | | | | |
| DV | AI | 20029 | US99 | Search Report | | | | |
| DV | AJ | 20030 | US99 | Search Report | | | | |
| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | | |
| DV | AK | | Ralls, Kenneth M., "Introduction to Materials Science and Engineering", John Wiley & Sons, © 1976, pp. 312-313 | | | | | |
| DV | AL | | Ravi K. Lax.an, "Synthesizing Low-k CVD Materials for Fab Use", Semiconductor International, Nov. 2000, 10 pps. | | | | | |
| DV | AM | | Anonymous, "New gas helps make faster IC's, Machine Design Cleveland, © Penton Media, Inc., November 4, 1999, pp. 118 | | | | | |
| DV | AN | | Lobada et al, "Using Trimethylsilane to Improve Safety Throughput and Versatility in PECVD Processes", 4th International Symposium on Silicon Nitride and Silicon Dioxide Thin Insulating Films, The Electrochemical Society, Abstract No. 358, p. 454, May 1997. | | | | | |
| DV | AO | | ARTICLE: Bencher, C. et al., "Dielectric antireflective coatings for DUV lithography", Solid State Technology (March 1997), pp. 109-114. | | | | | |
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| DV | AQ | | TEXT: Heavens, O. S., "Optical Properties of Thin Solid Films", pp. 48-49. | | | | | |
| EXAMINER <i>Shalard</i> | | | | DATE CONSIDERED <i>10/11/01</i> | | | | |
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| LIST OF ART CITED BY APPLICANT <small>(Use additional sheets if necessary)</small> | | | | | APPLICANT Weimin Li | | | |
| | | | | | FILING DATE January 20, 1999 | | GROUP 2818 | |
| U.S. PATENT DOCUMENTS | | | | | | | | |
| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | | |
| DV | AA | 09/146,842 | 9/3/98 | Yin et al | | | | |
| DV | AB | 09/146,843 | 9/3/98 | Li et al | | | | |
| DV | AC | 09/030,618 | 2/25/98 | Holscher et al | | | | |
| | AD | | | | | | | |
| | AE | | | | | | | |
| | AF | | | | | | | |
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| EXAMINER <i>Steward</i> | | | | DATE CONSIDERED <i>10/11/01</i> | | | | |
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| *Examiner Initial | | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
|-------------------|----|-----------------|-------|----------------|-------|----------|----------------------------|
| DV | AA | 4,474,975 | 10/84 | Clemons et al. | | | |
| | AB | | | | | | |
| | AC | | | | | | |
| | AD | | | | | | |
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| DV | AO | | M. Matsuura et al.; "A Highly Reliable Self-planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects"; July 1997; |
| | | | pp. 31.6.1-31.6.4 |
| DV | AP | | O. Horie et al.; "Kinetics and Mechanism of the Reactions of O ₂ P with SiH ₄ , CH ₃ SiH ₃ , (CH ₃) ₂ SiH ₂ , and (CH ₃) ₃ SiH"; The Journal of Physical Chemistry, Vol. 95, No. 11, 1991; pp. 4393-4400 |
| DV | AQ | | Robert Withmall et al.; "Matrix Reactions of Methylsilanes and Oxygen Atoms"; The Journal of Physical Chemistry, Vol. 92, No. 3, 1988; |
| | | | pp. 594-602 |
| DV | AR | | Ajeet M. Joshi et al.; "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography"; SPIE Vol. 1925, 1993; pp. 709-720 |

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200. Form PTO-101

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U.S. PATENT DOCUMENTS

| *Examiner Initial | | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
|-------------------|----|-----------------|------------------|---|-------|----------|----------------------------|
| DV | AA | 5,314,724 | 05/1994 | Tsukane et al | | | |
| | AB | 5,376,591 | 12-94 10/1998 | Yamazaki et al Maeda et. al. | | | |
| | AC | 6,001,741 | 12/1999 | Alers | | | |
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| | AE | 5,786,039 | 7/1998 | Brouquet | | | |
| | AF | | | | | | |
| | AG | | | | | | |
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

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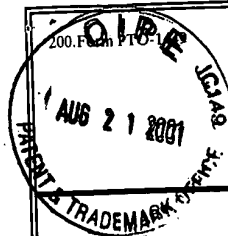
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2818

U.S. PATENT DOCUMENTS

| *Examiner Initial | | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
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| OV | AA | 5,314,724 | 05/1994 | Tsukane et al | | | |
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FOREIGN PATENT DOCUMENTS

| | | Document Number | Date | Country | Class | Subclass | Translation | |
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